

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

N. KOFUJI et al

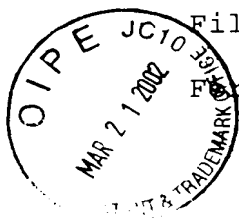
Serial No. 09/363,191

Group Art Unit: 1763

Filed: July 29, 1999

Examiner: L. Alejandro Mulero

For: DRY ETCHING APPARATUS AND A METHOD OF
MANUFACTURING A SEMICONDUCTOR DEVICE



PRELIMINARY AMENDMENT

Commissioner of Patents
Washington, D.C. 20231

Sir:

In response to the Office Action dated December 21, 2001,
please amend the above-identified application as follows. A
Continued Prosecution Application (CPA) Request is being filed
concurrently herewith by Applicants.

IN THE CLAIMS

Cancel claims 5 and 10-33 without prejudice or
disclaimer; amend claim 1; and add new claims 34-36 as
follows:

34. (New) A dry etching apparatus for treating a
semiconductor wafer comprising:

a chamber;

a holder in said chamber to receive a semiconductor
wafer;

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TC 1700